

ELECTROPLATING PROCESS CHAMBER  
WITH PRE-WETTING AND RINSING CAPABILITY

Jonathan D. Reid

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Steven W. Taatjes

Robert J. Contolini

Evan E. Patton

10 ABSTRACT OF THE DISCLOSURE

A plating cell has an inner plating bath container for performing electroplating on a work piece (e.g., a wafer) submerged in a solution contained by the inner  
15 plating bath container. A reclaim inlet funnels any solution overflowing the inner plating bath container back into a reservoir container to be circulated back into the inner plating bath container. A waste channel is also provided having an inlet at a different height  
20 than the inlet of the reclaim channel. After electroplating, the wafer is lifted to a position and spun. While spinning, the wafer is thoroughly rinse with, for example, ultra pure water. The spin rate and height of the wafer determine whether the water and  
25 solution are reclaimed through the reclaim channel or disposed through the waste channel.